

Removal of Fine Particle using SAPS Technology and Functional Water

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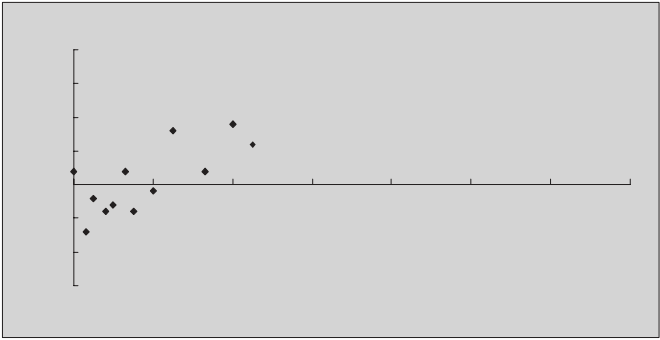
² Hynix Semiconductor

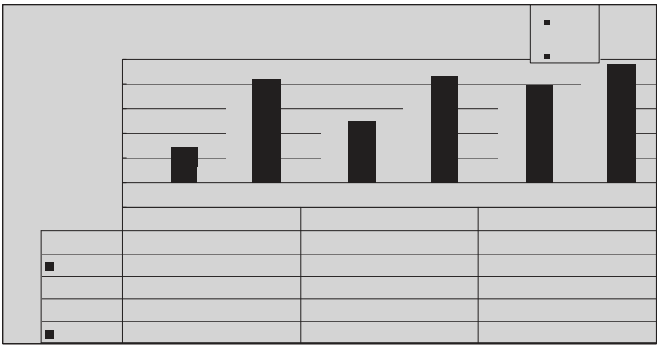
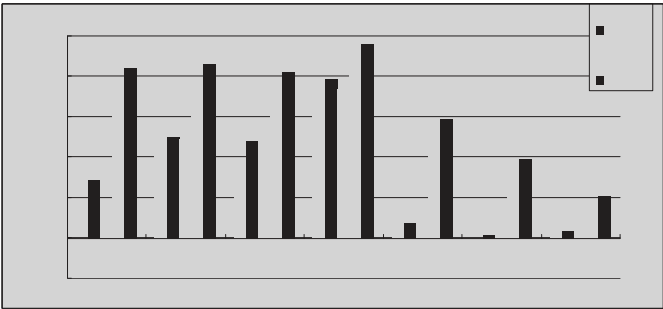
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I

Term	t Ratio					
N2(3,14)	-1.588785					
NH4OH*MegaPower	1.430211					
N2*NH4OH	1.328053					
MegaPower(5,20)	-0.929195					
NH4OH(5,30)	-0.668952					
NH4OH*NH4OH	0.507691					
MegaPower*MegaPower	-0.258493					
N2*N2	-0.207414					
N2*MegaPower	0.153237					





III

